

ABSTRACT

It is possible to detect with high precision a plurality of types of nonuniformity defects that occur in patterns formed on the surface of an examination object. A device (10) for examination of nonuniformity defects that has a light source (12) for emitting light to a photomask 50 whose surface is provided with a repeating pattern (51) in which unit patterns (53) are arrayed in a regular fashion, and a photodetector (13) for photodetecting and converting into photodetection data scattered light from the photomask, so that the photodetection data is observed to detect nonuniformity defects that have occurred in the repeating pattern, in the device further having a wavelength filter (14) for selecting and extracting one or a plurality of desired wavelength bands from the light of a plurality of wavelength bands, wherein nonuniformity defects of the repeating pattern are detected using the selected and extracted light of the wavelength band.